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RESPONSE UNDER 37C.F.R. 1.116  
-EXPEDITED PROCEDURE.  
EXAMINING GROUP 1507



In the United States Patent and Trademark Office

In re Application of:

Neil F. Haley, et al

RADIATION-SENSITIVE  
COMPOSITION CONTAINING A  
RESOLE RESIN, A NOVOLAC  
RESIN, AN INFRARED ABSORB-  
ER AND A TRIAZINE AND USE  
THEREOF IN LITHOGRAPHIC  
PRINTING PLATES

Serial No. 212,434

Filed 14 March 1994

Honorable Assistant Commissioner For Patents  
Washington, D.C. 20231

Sir:

AMENDMENT AFTER FINAL REJECTION

In response to the Office Action of August 7, 1995, please amend the above-identified application as follows:

In the Claims:

Please amend claim 1 as follows:

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1. (Amended) A radiation-sensitive composition useful for the preparation of an imaging layer of a lithographic printing plate that is sensitive to both ultraviolet and infrared radiation and capable of functioning in either a positive-working or negative-working manner; said radiation-sensitive composition comprising (1) a resole resin, (2) a novolac resin, (3) a haloalkyl-substituted S-triazine, and (4) an infrared absorber in amounts such that the solubility of said imaging layer in aqueous alkaline developing solution is reduced in exposed areas and increased in unexposed areas by the steps of imagewise exposure to activating radiation and heating.

Group Art Unit: 1507

Examiner: L. Weiner

I hereby certify that this correspondence is being deposited TODAY with the United States Postal Service as first class mail in an envelope addressed to Assistant Commissioner For Patents, Washington, D.C. 20231.

Alfred P. Lorenzo

Name

22503

Reg. No.

Signature

AUGUST 21, 1995

Date of Signature

#14/E  
W.M.  
#10475